

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Chih-Chien Liu, et al

Serial No: Unassigned

Filed: November 20, 2001

For: HIGH DENSITY PLASMA
CHEMICAL VAPOR DEPOSITION
PROCESS

Examiner: Unassigned

Art Unit: Unassigned

PRE Amend
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P.W.
1-23-02

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
2900 Crystal Drive
Arlington, VA 22202-3513

Sir:

Please amend the copy of U.S. Patent Application Serial No.
09/546,174 filed herewith, as follows:

IN THE SPECIFICATION:

On page 1, lines 12-13, please amend the specification according to
the attached sheets.

IN THE CLAIMS

Please cancel claims 1-20 without prejudice to the subject matter
recited therein.

Please add claims 21-31 according to the attached Clean Version of
the Amendment.

REMARKS

The amendment adds new claims 21-31 while canceling claims 1-20,
making claims 21-31 pending in the application. Support for the amendment
can be found in the parent application. No new matter has been added by the
amendment.